

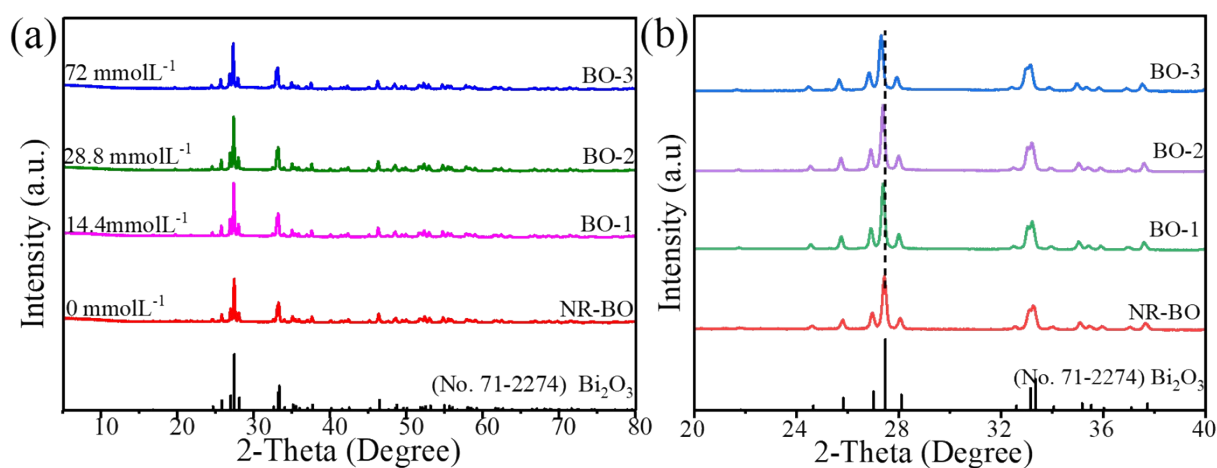


Fig. S1 XRD patterns of the obtained samples with different concentrations of nitric acid.

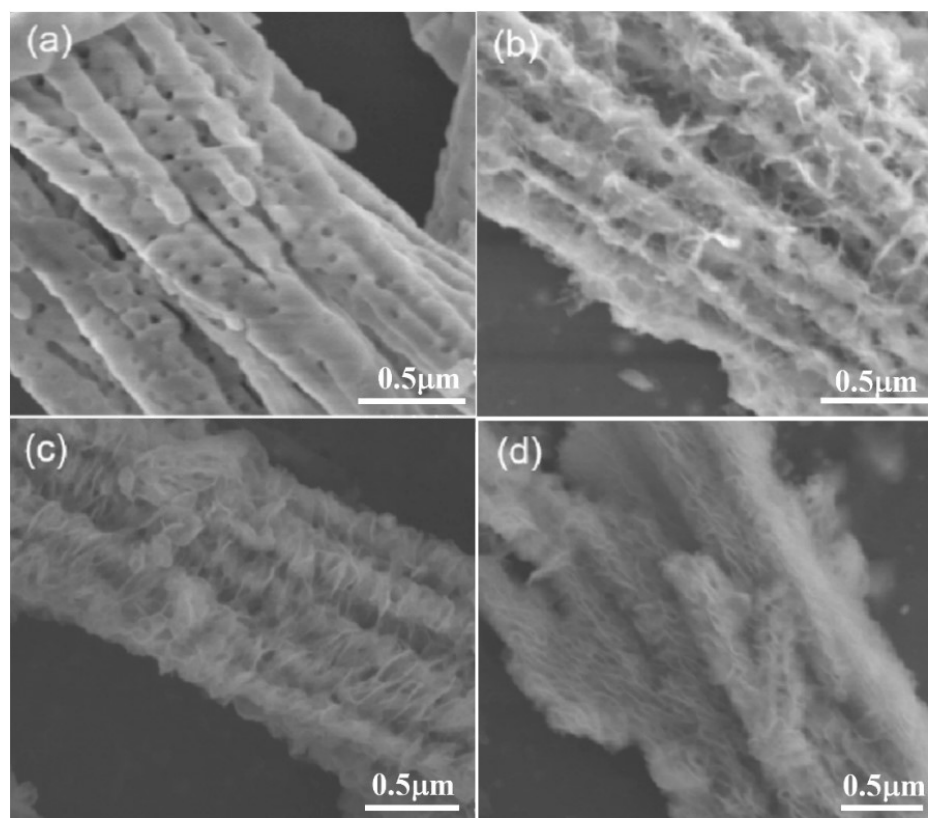


Fig. S2 SEM images of the obtained samples with different concentration of nitric acid, (a) 0 mmol • L⁻¹, (b) 14.4 mmol • L⁻¹, (c) 28.8 mmol • L⁻¹, (d) 72 mmol • L⁻¹.

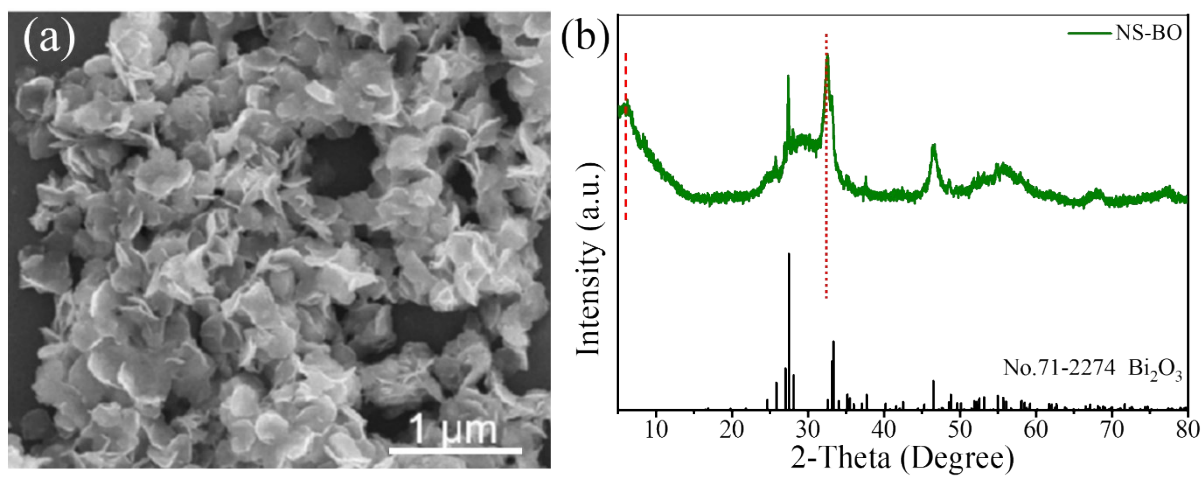


Fig. S3 SEM photographs (a) and XRD pattern (b) of BO-NS, $C_{\text{HNO}_3} = 288 \text{ mmol} \cdot \text{L}^{-1}$.

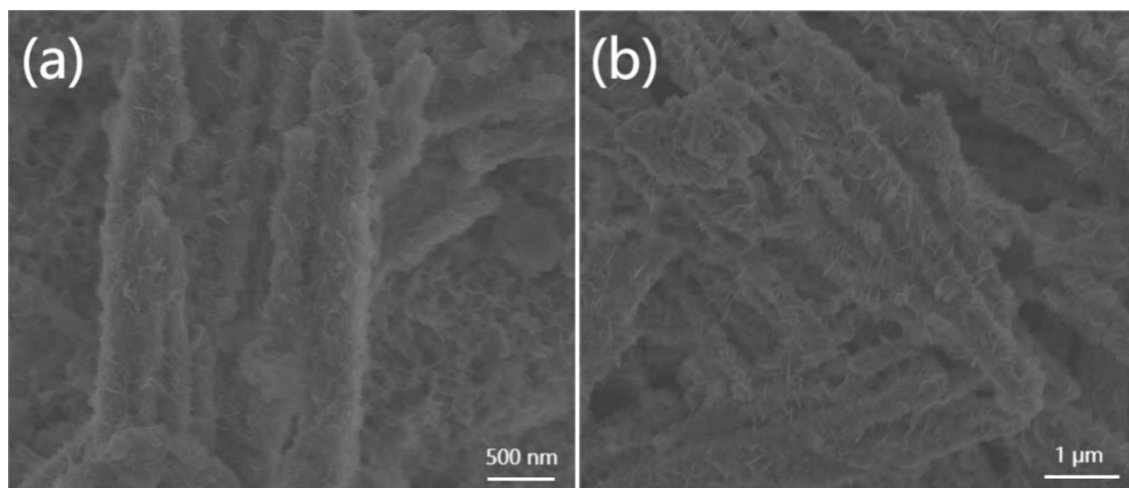


Fig. S4 SEM images of BO-2 synthesized at (a) 40 $^{\circ}\text{C}$ and (b) 60 $^{\circ}\text{C}$, respectively.

Table S1 Comparison of the photoreduction Cr (VI) (Xe lamp, 300 W).

Materials	Catalyst dosage (g/L)	C _{Cr(VI)} (mg/L)	Illumination time/ Reduction efficiency	k/ min ⁻¹	ref
Cl-doped Bi ₂ S ₃ homojunction	0.2	10	70 min/96.6%	0.036	[1]
0D/1D Bi ₂ MoO ₆	0.6	20	80 min/100%	0.024	[2]
α/γ In ₂ Se ₃	0.2	100	10 min/94.9%	0.239	[3]
p-n style TiO ₂	0.75	15	60 min/91%		[4]
In ₂ S ₃ Homojunction	0.4	20	30 min/98%	0.13	[5]
Bi ₄ V ₂ O ₁₁ Homojunction	0.5	10	100 min/87%		[6]
QDs self-decorated Bi ₂ MoO ₆	0.5	10	20 min/60%	0.047	[7]
Anatase-rutile TiO ₂	0.5	10	40 min/82%	0.046	[8]
Zn ₃ In ₂ S ₆ / Bi ₂ O ₃	0.5	10	120 min/99.8%	0.054	[9]
Bi ₂ O ₃ /CuBi ₂ O ₄ /Ag	0.4	10	30 min/96.9%	0.115	[10]
Bi ₂ O ₃ QDs/g-C ₃ N ₄	0.5	10	60 min/87.9%	0.033	[11]
Bi ₂ O ₃ /g-C ₃ N ₄	0.5	10	180 min/90%	0.01	[12]
Bi ₂ O ₃ /BiOI	0.2	20	100 min/94.5%		[13]
SnO ₂ / Bi ₂ O ₃ /BiOI	0.5	50	120 min/90%		[14]
P-doped BiO _x	0.5	5	180 min/84%		[15]
AgI/BiOI- Bi ₂ O ₃	1.0	10	90 min/98%	0.032	[16]
Bi ₂ O ₃ porous nanosphere	1.0	40	20 min/100%		[17]
Bi ₂ O ₃ /red P	0.25	40	30 min/99%	0.118	[18]
Bi ₂ O ₃ /Co ₃ O ₄ @C	0.8	20	120 min/100%		[19]
β - Bi ₂ O ₃ /BiOCl	1.0	50	18 min/100%		[20]
β - Bi ₂ O ₃ @Bi ₂ S ₃	0.5	20	60 min/100%		[21]
Bi ₂ O ₃	1.0	50	10 min/100%	0.331	[22]
α -Bi ₂ O ₃ / α -Bi ₂ O ₃	1.0	50	6 min/100%	0.657	This work
	1.0	100	12 min/100%	0.207	
	0.5	50	15 min/100%	0.166	

Table S2 Apparent rate contents (k) and BET surface area.

Samples	BET surface area ($\text{m}^2 \cdot \text{g}^{-1}$)	k(min^{-1})	k'(k/BET)
		Cr(VI)	Cr(VI)
BO-NR	7.9617	0.069	0.0087
BO-2	25.4538	0.657	0.0258
BO-3	43.8680	0.490	0.0112

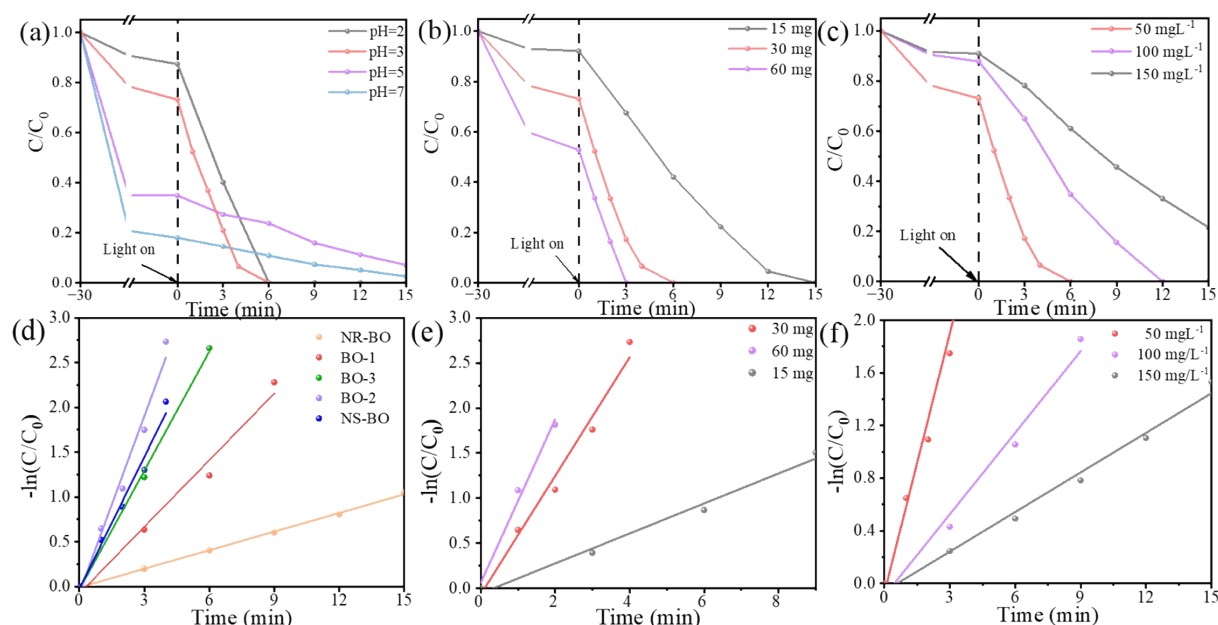


Fig. S5 (a) The reduction curve of Cr(VI) ($50 \text{ mg} \cdot \text{L}^{-1}$) at different pH values, (b) the effect of different dosage of BO-2 on reduction of Cr(VI) ($50 \text{ mg} \cdot \text{L}^{-1}$), (c) different concentrations Cr (VI) solutions with BO-2; The first-order kinetic curve for degrading Cr(VI). (d) Cr(VI) ($50 \text{ mg} \cdot \text{L}^{-1}$), (e) different amount of BO-2 photocatalyst, (f) different concentration of Cr(VI) using BO-2 (30 mg) as photocatalyst.

Table S3 Reaction rate contents (k) under different conditions.

	Cr(VI) (50 mg•L ⁻¹)			
	NR-BO	BO-1	BO-3	BO-2
k/min ⁻¹	0.06925	0.248	0.443	0.657
	Cr(VI) (50 mg•L ⁻¹)			
	15 mg (BO-2)	30 mg (BO-2)	60 mg (BO-2)	
k/min ⁻¹	0.166	0.657	0.907	
	30 mg BO-2 photocatalyst			
	50 mg•L ⁻¹ Cr(VI)	100 mg•L ⁻¹ Cr(VI)	150 mg•L ⁻¹ Cr(VI)	
k/min ⁻¹	0.657	0.207	0.100	

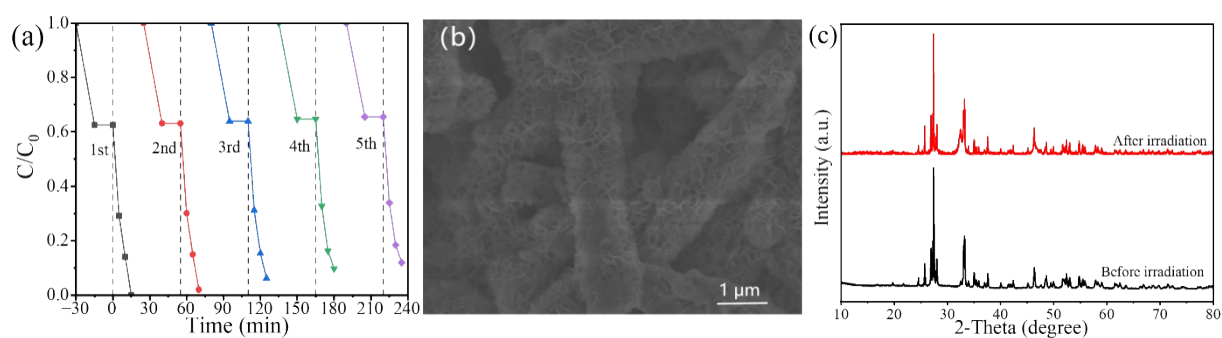


Fig. S6 (a) Cycling times for degrading Cr(VI) (50 mg•L⁻¹) with BO-2 photocatalyst, (b) SEM image and (c) XRD pattern of reducing Cr(VI) (50 mg•L⁻¹) by BO-2 sample under illumination light.

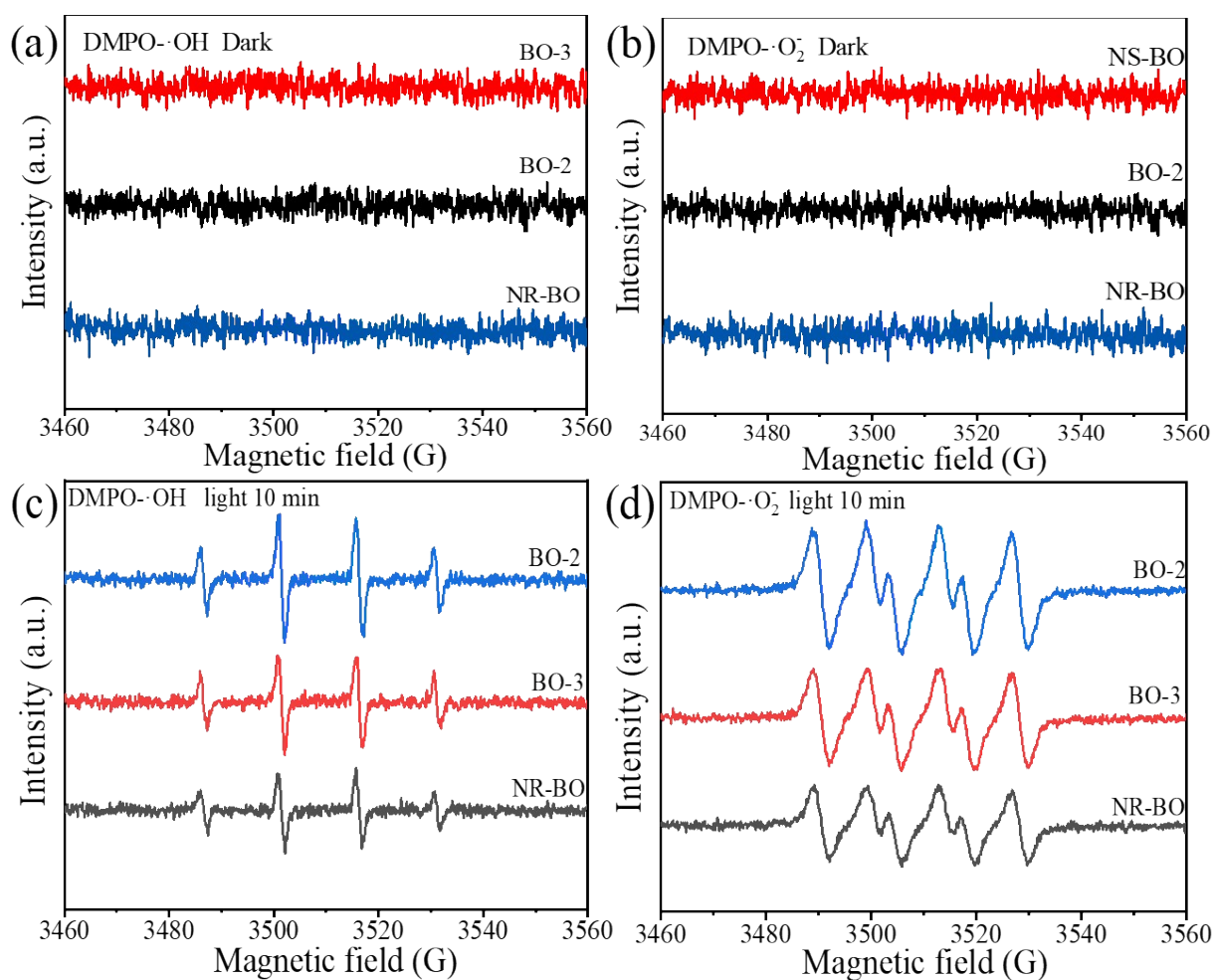


Fig. S7 In-situ ESR spectra of radical adducts trapped by (a,c) DMPO- $\cdot$ OH, (b,d) DMPO- $\cdot$ O₂⁻ in the obtained samples under dark and light irradiation.

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